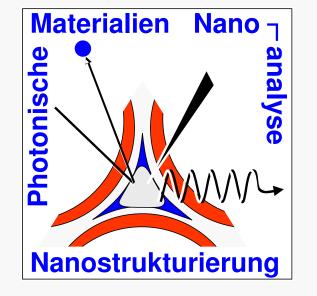
Morphology investigation of nanopores by block copolymer lithography on different material surfaces



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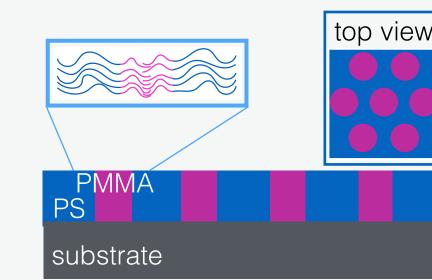
Motivation

Block copolymer (BCP) lithography for self-assembled thin film nanopatterning is known to strongly depend on the interactions between the polymer species of the BCP and the substrate surface. The system of PS-b-PMMA on SiO₂ surfaces is investigated for promising applications in semiconductor technology. A SiO₂ surface can, however, only be patterned by BCP lithography if the surface is neutralized, e.g. by a RCP brush, which then allows for pattern orientation control. For many other applications of BCP lithography materials other than SiO₂ are of interest. In particular, nanopatterned TiO₂ on Ti-6AI-4V alloys can be exploited in biomedicine.

Block copolymer lithography

Polymer thin films are patterned due to the microphase separation behavior of BCPs into self-assembled hexagonally arranged PMMA cylinders in a PS matrix.

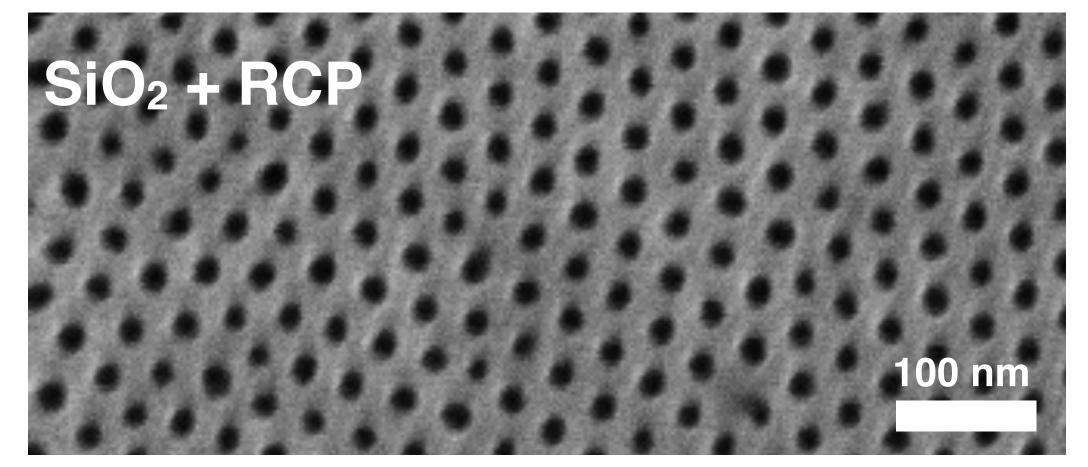
Review: R. A. Puglisi, Hindawi J. Nanomaterials, Art. ID 586458 (2015).



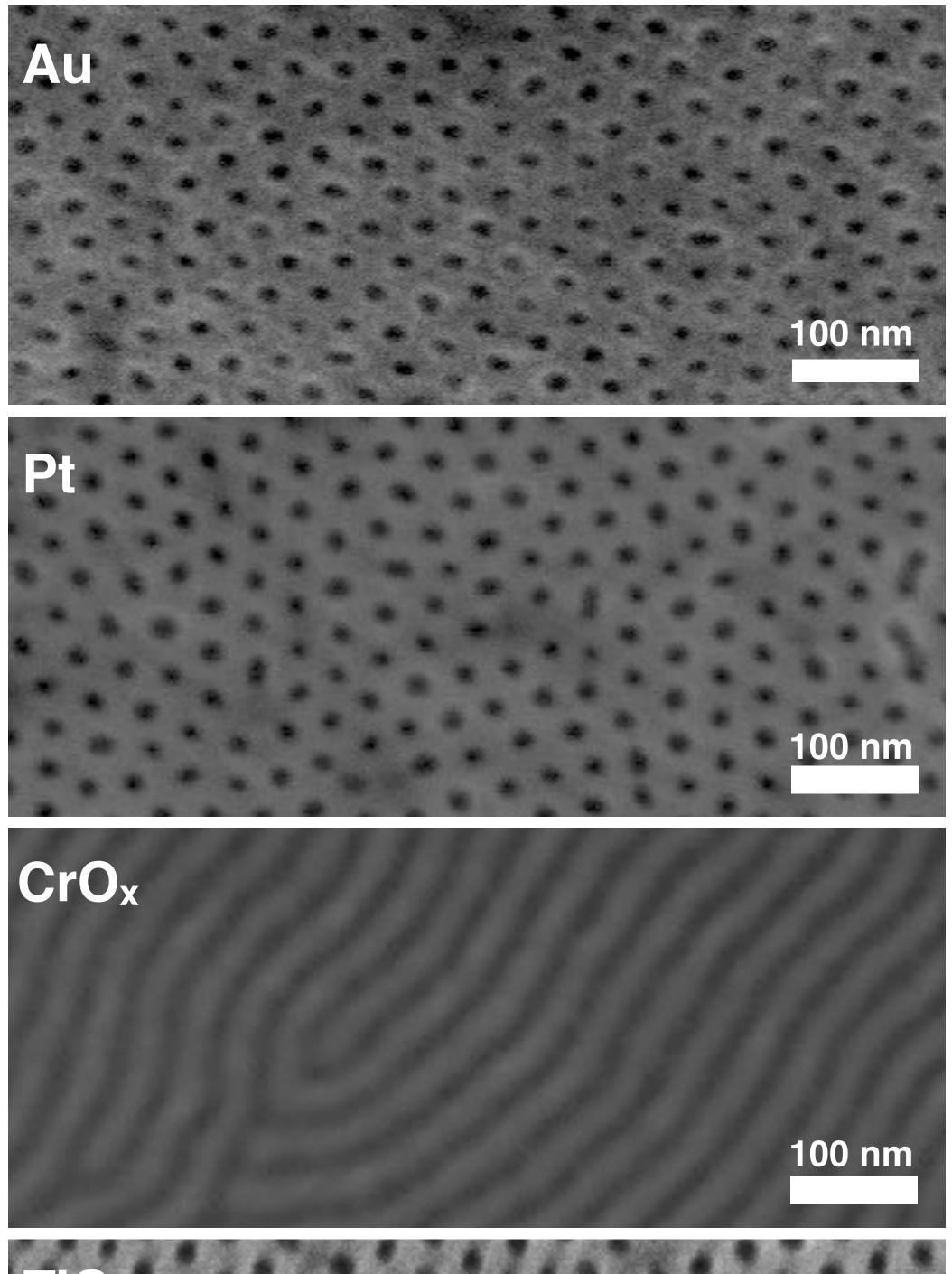
For PS films in all SEM images shown here:

- Polymer: PS-b-PMMA, block ratio 70:30, $M_n =$ 67 kg/mol, PDI = 1.09 (Polymer Source Inc.)
 - BCP film thickness 35 nm
 - Microphase separation induced by annealing at 180 °C at 10⁻³ mbar
- 254 nm UV light exposure and acetic acid to remove PMMA

F_{mix} is the mixing Gibbs free energy of the BCP (Flory Huggins The free energy of a polymer film on a substrate surface can be described by: theory), Felast the elastic energy, which changes with the chain conformation, and Finterface the interfacial energies of polymer species $F = F_{mix} + F_{elast} + F_{interface}$ A and B with each other, the substrate interface and the interface towards air/vacuum.



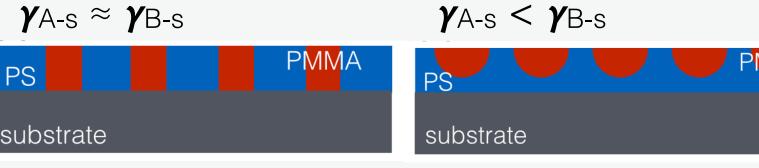




A. Andreozzi, E. Poliani, G. Seguini, M. Perego, Nanotechnology 22, 185304 (2011)

Influence of surface polarity

The interfacial energies γ between the polymer species A and B of the BCP and the substrate surface s are known to determine the orientation of nanopores formed during microphase separation. For equal interfacial energies between substrate and polymer A as well as polymer B, nanopores will be oriented perpendicularly to the surface. This is the desired orientation for most lithographical purposes. An interfacial energy with one polymer species much larger than with the other one, however, will result in preferential wetting of one polymer and thus a parallel orientation of nanostructures.



Influence of surface roughness

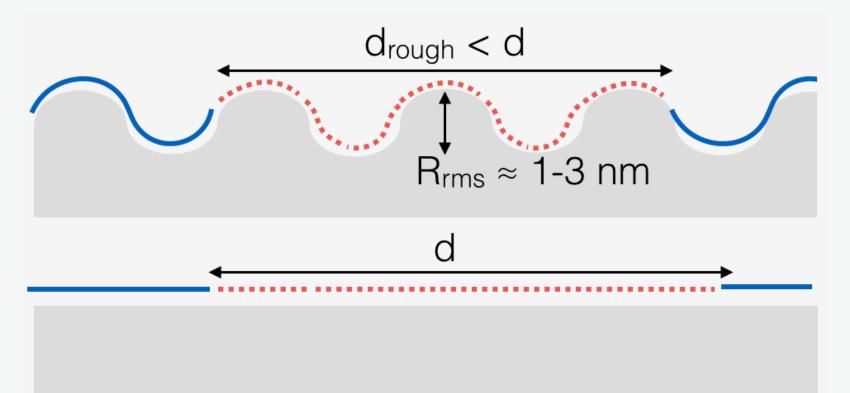
The comparison of BCP nanopores formed on smooth surfaces (roughness $R_{rms} < 1$ nm, all SEM images in left column) with those formed on rough surfaces ($R_{rms} > 1$ nm, SEM image below) reveals that nanopore diameters decrease and their shape becomes less defined on rough surfaces. For Pt, the average diameters change from d = 17.4 ± 3.2 nm (at R_{rms} = 0.6 nm) of to d_{rough} = 15.7 ± 2.4 nm (at $R_{rms} = 1.6$ nm) as apparent in top view SEM. rough Pt 00 nm

	SiO ₂ + RCP	SiO ₂	Au	Pt	CrO _x	TiO ₂
SFE [mN/m]	39	48	46	40	48	39
Polar	9 %	46 %	0.1 %	12 %	28 %	7 %

Our investigations show, that in particular the polar fraction of the substrate surface energy determines the nanopore orientation. Surfaces such as SiO₂ or CrO_x, which have a partially polar character, are not neutral to PS and PMMA, thus parallel nanostructures are formed. On predominantly dispersive surfaces, perpendicular nano-pores form, e.g. on Au, TiO₂, Pt, or RCPfunctionalized substrates.



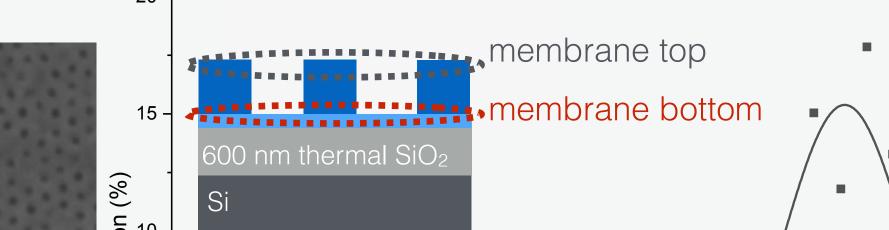
We believe that the decreased nanopore size drough results from an adjustment of the chain conformation according to surface roughness, if R_{rms} is in the size regime of the polymer radius of gyration R_g.

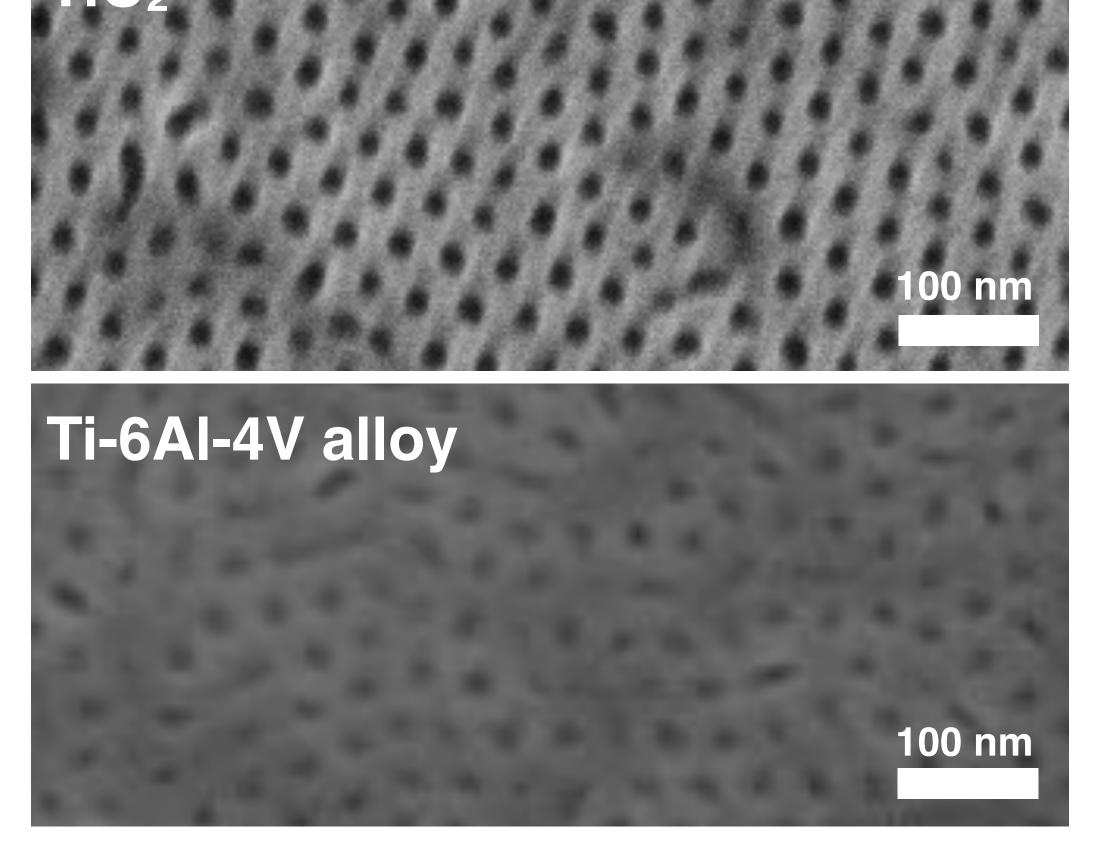


BCP membrane - top and bottom

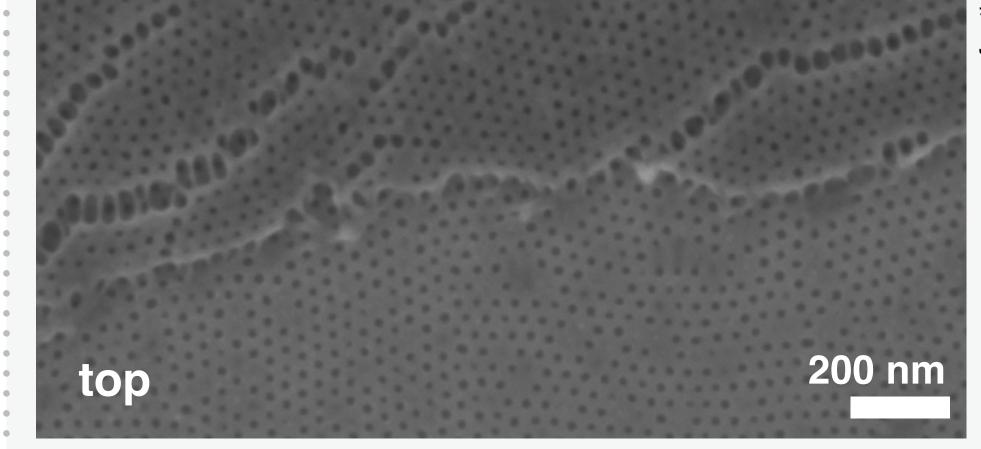
bottom

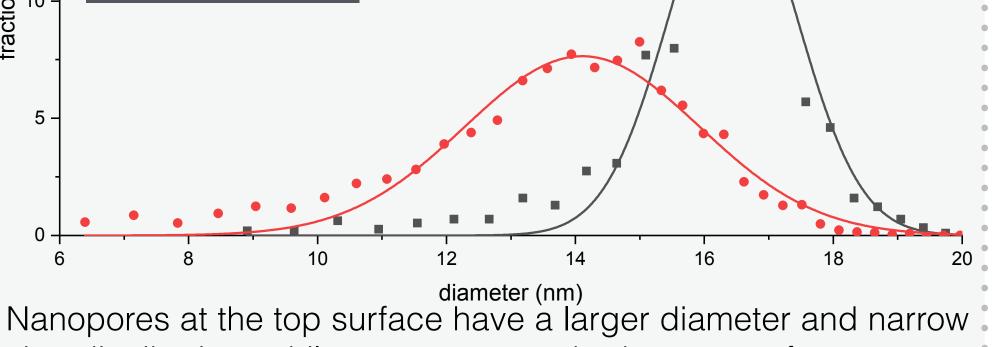
In order to investigate the nanopore morphology throughout the thin film, BCP lithography was performed on a 600 nm thick sacrificial thermal SiO₂ layer (functionalized with RCP). Etching of the SiO₂ with HF (5%, aq) results in the release of the nanopatterned PS film (25 nm thickness). The floating membrane was skimmed with a Si wafer. The SEM image below shows a folded part of the membrane, revealing its former top interface to air and bottom interface to the SiO₂ surface.





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size distribution, while nanopores at the bottom surface appear smaller with broad distribution. Besides possible RCP residuals, this is likely to result from the influence of the interfaces and could suggest a conical nanopore shape.

For more information see our latest publication:

Hierarchical nanopores formed by block copolymer lithography on surfaces of different materials pre-patterned by nanosphere lithography

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